

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	9698	polymer and photoresist and etch\$ and metal and oxygen	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 09:22
L2	4108	I1 and (clean\$3 or rins\$3) and water	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 09:23
L3	3610	I2 and oxid\$5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 09:24
L4	12	I3 and (pure adj3 (water and oxygen))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 09:28
L5	11	I3 and (polymer adj3 ashing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 09:57
L6	27	I3 and (polymer near oxygen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 11:45
L7	27	I6 not I5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 09:58
L8	5	I3 and (polymer near oxygen).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/24 11:45